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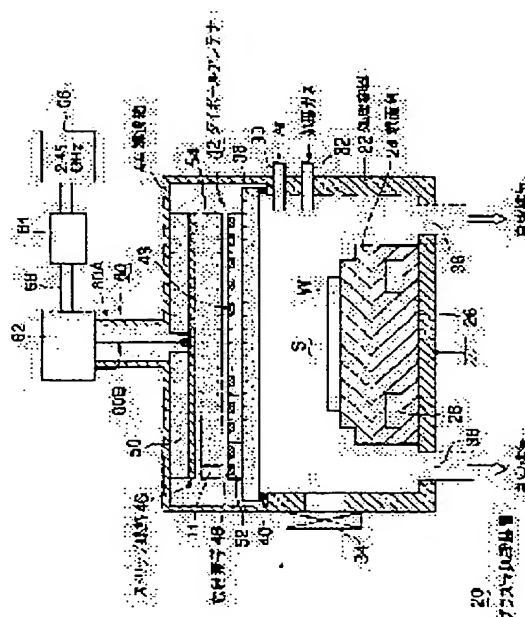
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## (54) PLASMA PROCESSING SYSTEM

## (57)Abstract:

PROBLEM TO BE SOLVED: To provide a plasma processing system having a relatively simple structure.

SOLUTION: A plasma is generated by introducing high frequency power into an evacuated container 22 and an object W to be processed is subjected to a specified processing using the plasma. In such a plasma processing system, a dipole antenna 42 is provided at the ceiling of the processing container in order to introduce high frequency power into the container. According to the arrangement, the structure is simplified relatively.



## LEGAL STATUS

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